L Number	Hits	Search Text	DB	Time stamp
1	1493	(rta or rtp or rapid near2 thermal or	USPAT;	2004/04/22 09:52
		thermal near2 processing or anneal or	US-PGPUB;	
		annealer or annealing) and (quartz near	EPO; JPO;	
		tube)	DERWENT;	
			IBM_TDB	
2	334		USPAT;	2004/04/22 10:51
	İ	thermal near2 processing or anneal or	US-PGPUB;	
		annealer or annealing) and (quartz near	EPO; JPO;	
		tube) and (wafer or tray or carrier or	DERWENT;	
		holder or chuck or support) near3 (alignment	IBM_TDB	
		or aligning or aligned or align or position		
		or positioning or positioner or positioned or locating or location or groove or notch		
		or quide)		
3	11559	1 2 .	USPAT;	2004/04/22 11:44
	11333	thermal near2 processing or anneal or	US-PGPUB;	2004/04/22 11.44
		annealer or annealing) and (wafer or	EPO; JPO;	
		substrate) near2 (alignment or aligning or	DERWENT;	
		aligned or align or position or positioning	IBM_TDB	
		or positioner or positioned or locating or	_	
		location or groove or notch or guide)		
4	127	,	USPAT;	2004/04/22 11:01
		thermal near2 processing or rapid near2	US-PGPUB;	
İ		anneal\$3) and (wafer or substrate) near2	EPO; JPO;	
		(alignment or aligning or aligned or align	DERWENT;	
		or position or positioning or positioner or	IBM_TDB	
		positioned or locating or location) near3		
	,	(notch or groove or guide or depression or recess)		
5	105		USPAT;	2004/04/22 11:45
"	103	thermal near2 processing or anneal or	US-PGPUB;	2004/04/22 11:45
		annealer or annealing) and (quartz or	EPO; JPO;	
		furnace or housing) near tube same (wafer or	DERWENT;	
		substrate) near2 (alignment or aligning or	IBM TDB	
		aligned or align or position or positioning	_	
		or positioner or positioned or locating or		
		location or groove or notch or guide)		
6	44	(rta or rtp or rapid near2 thermal or	USPAT;	2004/04/22 11:53
		thermal near2 processing) and (quartz or	US-PGPUB;	
		furnace or housing) near tube same (wafer or	EPO; JPO;	
		substrate) near2 (alignment or aligning or	DERWENT;	
		aligned or align or position or positioning or positioner or positioned or locating or	IBM_TDB	
		location or groove or notch or guide)		
7	0	(rta or rtp or rapid near2 thermal or	USOCR	2004/04/22 11:53
	ľ	thermal near2 processing) and (quartz or	CDOCK	2001/01/22 11:55
		furnace or housing) near tube same (wafer or		
		substrate) near2 (alignment or aligning or		
		aligned or align or position or positioning		
		or positioner or positioned or locating or		
		location or groove or notch or guide)		
8	836	(rta or rtp or rapid adj thermal adj	USPAT;	2004/04/22 11:54
		anneal\$3 or rapid adj thermal adj	US-PGPUB;	
		process\$3).ti.	EPO; JPO;	
			DERWENT;	
9	1 1 1	(who are who are world and the court and	IBM_TDB	0004/04/55 55 55
"	11	(rta or rtp or rapid adj thermal adj	USPAT;	2004/04/22 11:58
		anneal\$3 or rapid adj thermal adj	US-PGPUB;	
		process\$3).ti. and (positioning or position or positioned or positioner or alignment or	EPO; JPO;	
		aligning or aligner or align or location or	DERWENT; IBM TDB	
		locating or locater or located or placement	10.1-100	
		or placing or placed) near4 (notch or groove		
		or depression or guide or rail)		
		<u> </u>	L	

10	209	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locater or located or placement or placing or placed or notch or groove or guide) near4 (wafer or substrate or sample or holder or tray or carrier or chuck or support)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:59
11	172	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or location or locating or locater or located or placement or placing or placed or notch or groove or guide) near2 (wafer or substrate or sample or holder or tray or carrier or chuck or support)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 11:59
12	129		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:51
13 14		("5445676" "5710407").PN. 6051512.URPN.	USPAT	2004/04/22 12:15
15		438/663.ccls.	USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/22 12:16 2004/04/22 12:53
16	764	219/390.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/22 12:33
17	136	219/390.ccls. and (rta or rtp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:33
18	14	(rta or rtp or rapid adj thermal adj anneal\$3 or rapid adj thermal adj process\$3).ti. and (positioning or position or positioned or positioner or alignment or aligning or aligner or align or locating or locater or located or placement or placing or notch or groove or guide) near2 (susceptor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:52
19	659	438/795.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 12:52
20	114	438/795.ccls. and (rta or rtp)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/04/22 12:52
21	25	438/663.ccls. and (quartz or tube)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/22 12:53